

EE 530 Eletrônica Básica I

Física dos Transistores de Efeito de Campo (FET)

Prof. Pedro Xavier

Resposta exercício-aula passada

- Corrente de dreno $v = -\mu_n E$

$$I = Q \cdot v$$

$$v = +\mu_n \frac{dV}{dx}$$

$$Q(x) = WC_{ox} [V_{GS} - V(x) - V_{TH}]$$

$$I_D = WC_{ox} [V_{GS} - V(x) - V_{TH}] \mu_n \frac{dV(x)}{dx}$$

$$\int_0^L I_D dx = \int_0^{V_{DS}} WC_{ox} [V_{GS} - V(x) - V_{TH}] \mu_n dV$$

$$I_D L = \mu_n C_{ox} W \left[\int_0^{V_{DS}} [V_{GS} - V_{TH}] dV - \int_0^{V_{DS}} V(x) dV \right]$$

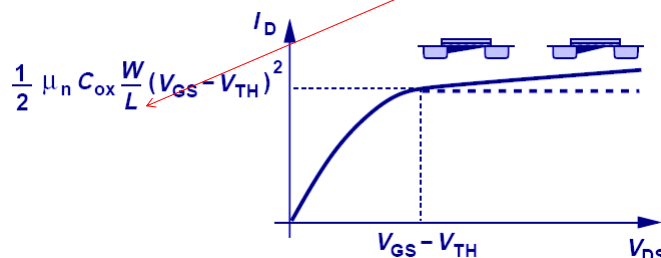
$$I_D = \mu_n C_{ox} \frac{W}{L} \left[[V_{GS} - V_{TH}] V_{DS} - \frac{V_{DS}^2}{2} \right]$$

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} [2(V_{GS} - V_{TH}) V_{DS} - V_{DS}^2]$$

μ : mobilidade dos portadores
[cm²/(V·s)]

Modulação do comprimento do canal

- O aumento de V_{DS} , causa um aumento do estrangulamento do canal, diminuindo seu comprimento efetivo (L).
- I_D aumenta com V_{DS}



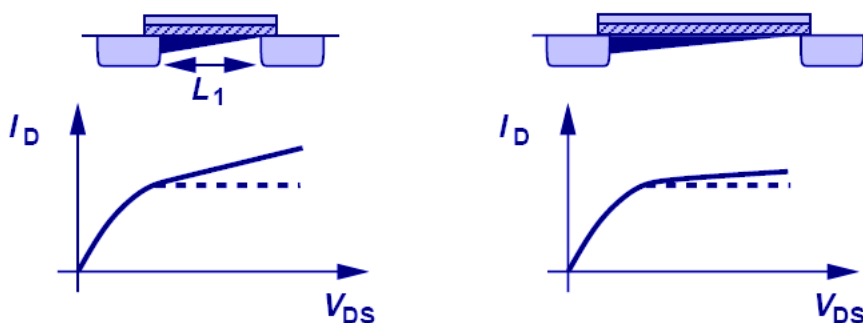
$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2 (1 + \lambda V_{DS})$$

λ : coeficiente de modulação do comprimento do canal

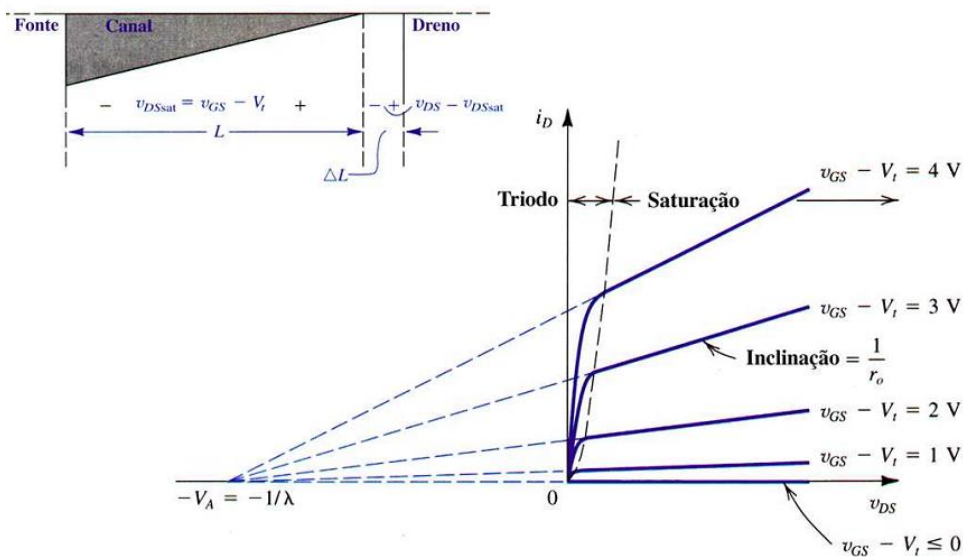
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Modulação do comprimento do canal

- Relação $\lambda - L$
 - O efeito da modulação do comprimento do canal é menor, quanto maior o L .
 - $\lambda \propto 1/L$



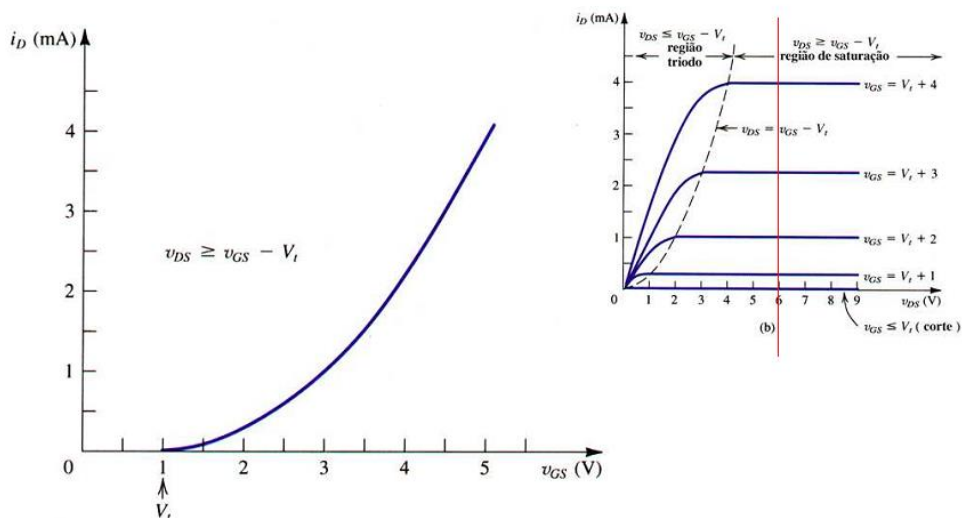
Modulação do comprimento do canal



Modulação do comprimento do canal

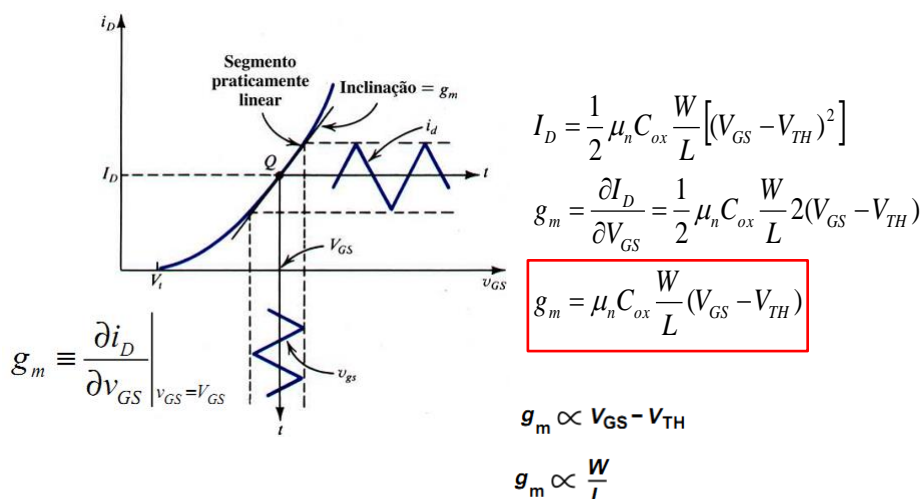
- Exercício: $I_D = 1 \text{ mA}$ para $V_{DS} = 5 \text{ V}$ ($\lambda = 0,1 \text{ V}^{-1}$). Calcule de quanto I_D varia, se V_{DS} for aumentado de 1V. Qual é a impedância de saída?

Característica $i_D - v_{GS}$ do NMOS na saturação



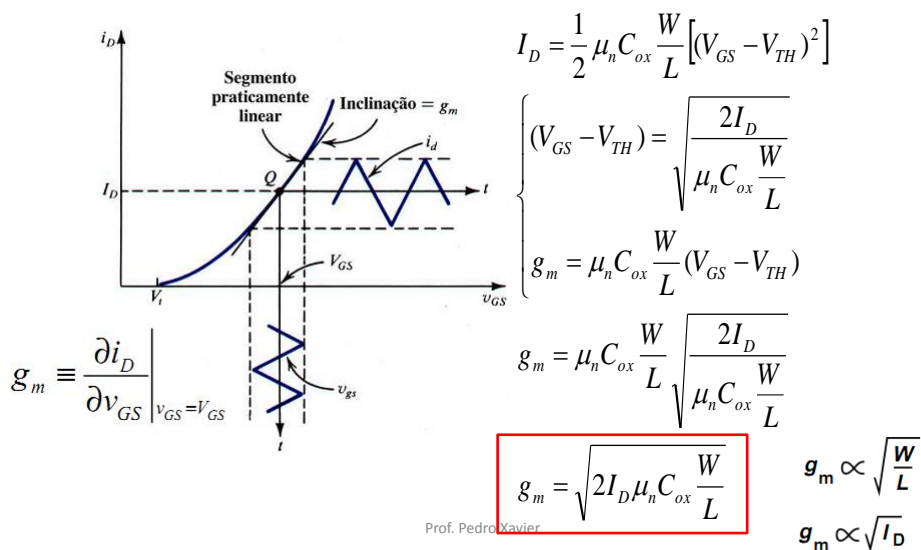
$$V_t = 1 \text{ V e } k'_n(W/L) = 0.5 \text{ mA/V}^2 \quad i_D = \frac{1}{2} k'_n \frac{W}{L} (v_{GS} - V_t)^2$$

Transcondutância MOS (saturação)

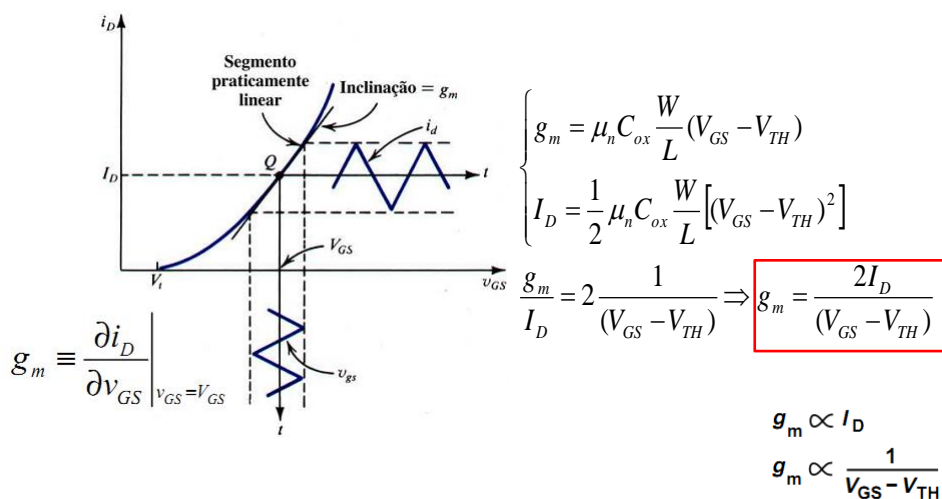


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Transcondutância MOS (saturação)

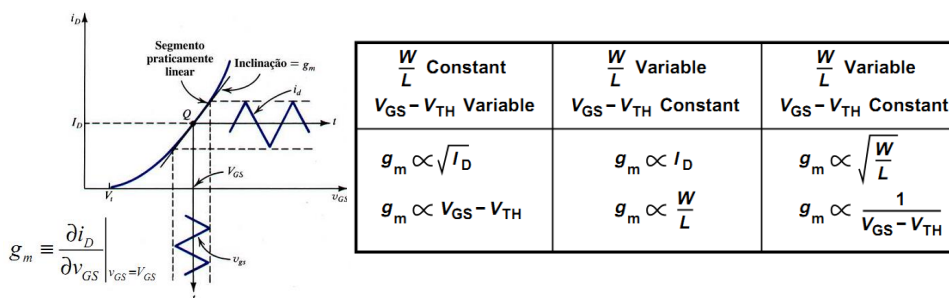


Transcondutância MOS (saturação)



Transcondutância MOS (saturação)

- Resumo



$$g_m = \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})$$

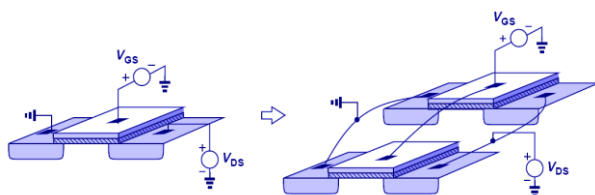
$$g_m = \sqrt{2\mu_n C_{ox} \frac{W}{L} I_D}$$

$$g_m = \frac{2I_D}{V_{GS} - V_{TH}}$$

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Transcondutância MOS (saturação)

- Ao dobrarmos a largura (W), colocando 2 FETs em paralelo, dobramos I_D , portanto g_m , também, dobra.

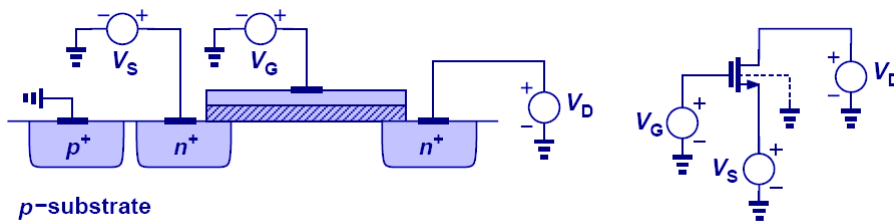


$$g_m = \frac{2I_D}{V_{GS} - V_{TH}}$$

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Efeito de Corpo

Quando $V_S \neq V_B$ (tensão de corpo), V_{TH} é alterado.



$$V_{TH} = V_{TH0} + \gamma \left(\sqrt{2\phi_F + V_{SB}} - \sqrt{2\phi_F} \right)$$

V_{TH0} : Tensão limiar para $V_{SB}=0$

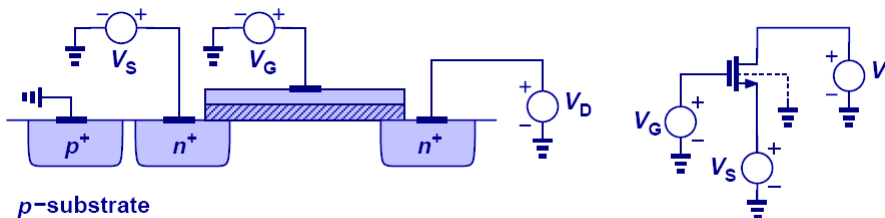
γ e ϕ_f : parâmetros dependentes da tecnologia

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$$\gamma = \frac{\sqrt{2qN_A\epsilon_S}}{C_{ox}}$$

Efeito de Corpo

Determine I_D . $V_S=0.5V$; $V_G=V_D=1.4V$; $\mu_n C_{ox}=100\mu A/V^2$; $W/L=50$;
 $V_{TH0}=0.6V$; $\gamma=0.4$; $\phi_f=0.4$; $\lambda=0$.



$$V_{TH} = V_{TH0} + \gamma \left(\sqrt{2\phi_F + V_{SB}} - \sqrt{2\phi_F} \right)$$

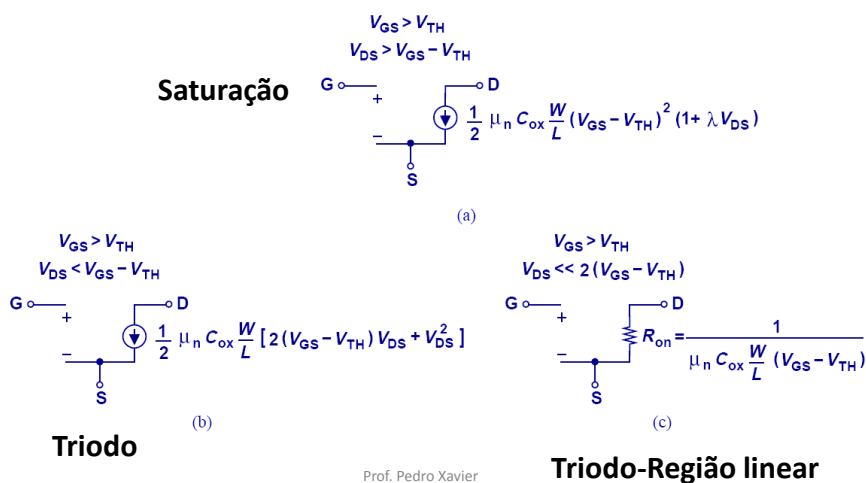
V_{TH0} : Tensão limiar para $V_{SB}=0$

γ e ϕ_f : parâmetros dependentes da tecnologia

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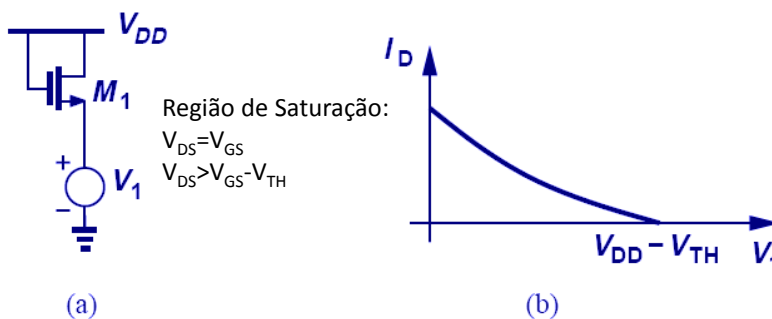
$$\gamma = \frac{\sqrt{2qN_A\epsilon_S}}{C_{ox}}$$

Modelo de Grandes Sinais



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Exemplo

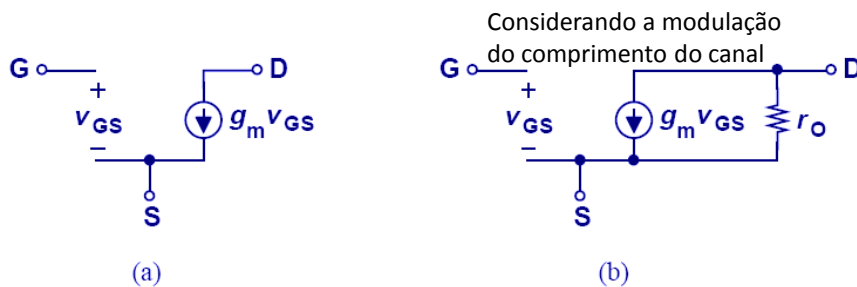


$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2$$

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{DD} - V_1 - V_{TH})^2$$

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Modelo de Pequenos Sinais



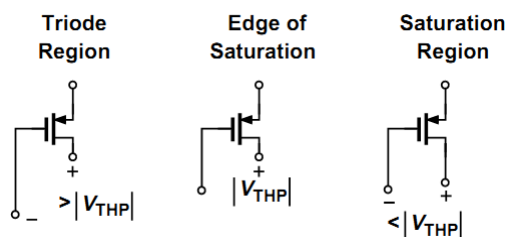
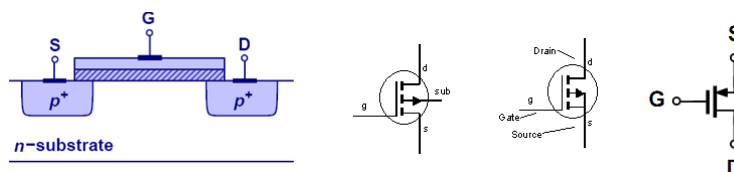
$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2 (1 + \lambda V_{DS})$$

$$r_o = \left(\frac{\partial I_D}{\partial V_{DS}} \right)^{-1} = \frac{1}{\frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2 \lambda}$$

$$r_o = \frac{1}{\lambda I_D}$$

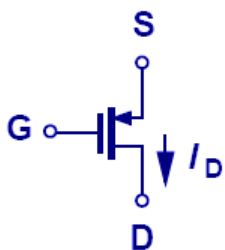
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Transistor PMOS



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Transistor PMOS - Equações



$$I_{D,sat} = \frac{1}{2} \mu_p C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2 (1 - \lambda V_{DS})$$

$$I_{D,tri} = \frac{1}{2} \mu_p C_{ox} \frac{W}{L} [2(V_{GS} - V_{TH})V_{DS} - V_{DS}^2]$$

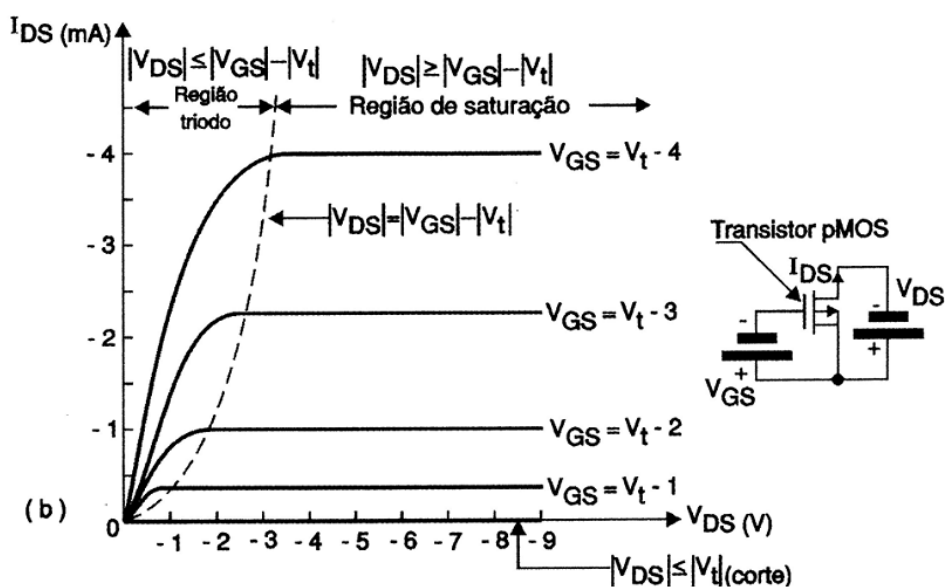
$$I_{D,sat} = \frac{1}{2} \mu_p C_{ox} \frac{W}{L} (|V_{GS}| - |V_{TH}|)^2 (1 + \lambda |V_{DS}|)$$

$$I_{D,tri} = \frac{1}{2} \mu_p C_{ox} \frac{W}{L} [2(|V_{GS}| - |V_{TH}|)|V_{DS}| - V_{DS}^2]$$

Obs: O modelo de pequenos sinais é o mesmo

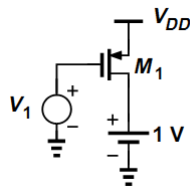
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Característica $i_D - v_{DS}$ para o PMOS



Exemplo 6.15 - Razavi

- Determine a região de operação de M1, de acordo com V_1 (V_{DD} a 0V).

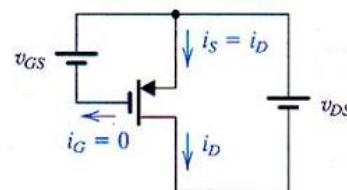
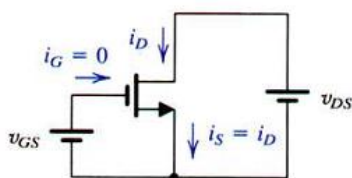


$$V_{DD} = 2.5 \text{ V}$$

$$|V_{TH}| = 0.5 \text{ V}$$

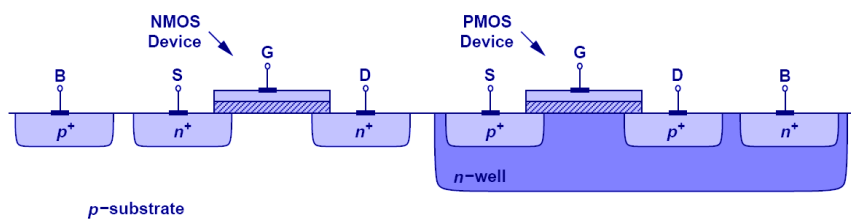
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Comparação PMOS - NMOS



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CMOS (MOS COMPLEMENTAR)



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Comparação MOSFET - TBJ

Bipolar Transistor	MOSFET
Exponential Characteristic Active: $V_{CB} > 0$ Saturation: $V_{CB} < 0$ Finite Base Current Early Effect Diffusion Current -	Quadratic Characteristic Saturation: $V_{DS} > V_{GS} - V_{TH}$ Triode: $V_{DS} < V_{GS} - V_{TH}$ Zero Gate Current Channel-Length Modulation Drift Current Voltage-Dependent Resistor

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Fontes de figuras da aula

- Aula do prof. Fabiano Fruett
- Fundamentos de Microeletrônica (Razavi)
- Microeletrônica (Sedra)

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Sugestão de estudo

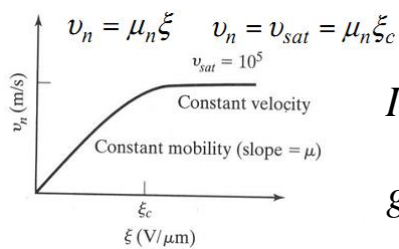
- Razavi, Cap. 6
- Sedra/Smith cap. 5 seções 5.1 até 5.3
 - Exercícios e problemas correspondentes

Para saber mais:

Paul R. Gray e Robert G. Meyer, Analysis and Design of Analog integrated Circuits, John Wiley & Sons

T. Tsvividis, Design considerations in single-channel MOS analog integrated circuits – A tutorial”, IEEE JSSC SC 13, pp 383-391, junho de 1978

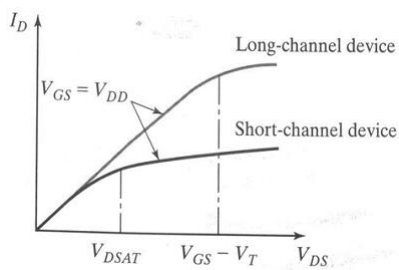
Efeito da Velocidade de Saturação em Transistores com o Canal Curto



$$Q = WC_{ox}(V_{GS} - V_{TH})$$

$$I_D = v_{sat} \cdot Q = v_{sat} \cdot WC_{ox}(V_{GS} - V_{TH})$$

$$g_m = \frac{\partial I_D}{\partial V_{GS}} = v_{sat} WC_{ox}$$



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